

10784510_CLS
Most Frequently Occurring Classifications of Patents Returned
From A Search of 10784510 on September 02, 2004

Original Classifications

11 250/492.2
6 250/492.21
3 250/309
2 250/252.1
2 250/281
2 250/283
2 250/492.3
2 359/484

Cross-Reference Classifications

12 250/397
9 250/398
5 250/492.3
3 250/281
3 250/282
3 250/288
3 250/492.2
3 315/111.81
2 118/715
2 250/251
2 250/298
2 250/423R
2 250/443.1
2 313/361.1
2 313/363.1
2 359/324

Combined Classifications

14 250/492.2
13 250/397
9 250/398
7 250/492.3
6 250/492.21
5 250/281
4 250/288
3 250/251
3 250/282
3 250/283
3 250/309
3 250/423R
3 315/111.81
2 118/715
2 250/252.1

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2 250/298
2 250/443.1
2 313/361.1
2 313/363.1
2 324/71.3
2 359/324
2 359/484
2 378/160
2 427/523

10784510_CLSTITLES

Titles of Most Frequently Occurring Classifications of Patents Returned

From A Search of 10784510 on September 02, 2004

- 14 250/492.2 (11 OR, 3 XR)
Class 250 : RADIANT ENERGY
250/492.1 IRRADIATION OF OBJECTS OR MATERIAL
250/492.2 .Irradiation of semiconductor devices
- 13 250/397 (1 OR, 12 XR)
Class 250 : RADIANT ENERGY
250/396R WITH CHARGED PARTICLE BEAM DEFLECTION OR
FOCUSSING
250/397 .With detector
- 9 250/398 (0 OR, 9 XR)
Class 250 : RADIANT ENERGY
250/396R WITH CHARGED PARTICLE BEAM DEFLECTION OR
FOCUSSING
250/398 .With target means
- 7 250/492.3 (2 OR, 5 XR)
Class 250 : RADIANT ENERGY
250/492.1 IRRADIATION OF OBJECTS OR MATERIAL
250/492.3 .Ion or electron beam irradiation
- 6 250/492.21 (6 OR, 0 XR)
Class 250 : RADIANT ENERGY
250/492.1 IRRADIATION OF OBJECTS OR MATERIAL
250/492.2 .Irradiation of semiconductor devices
250/492.21 ..Ion bombardment
- 5 250/281 (2 OR, 3 XR)
Class 250 : RADIANT ENERGY
250/281 IONIC SEPARATION OR ANALYSIS
- 4 250/288 (1 OR, 3 XR)
Class 250 : RADIANT ENERGY
250/281 IONIC SEPARATION OR ANALYSIS
250/288 .With sample supply means
- 3 250/251 (1 OR, 2 XR)
Class 250 : RADIANT ENERGY
250/251 ELECTRICALLY NEUTRAL MOLECULAR OR ATOMIC BEAM
DEVICES AND METHODS
- 3 250/282 (0 OR, 3 XR)

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Class 250 : RADIANT ENERGY
 250/281 IONIC SEPARATION OR ANALYSIS
 250/282 .Methods

3 250/283 (2 OR, 1 XR)
 Class 250 : RADIANT ENERGY
 250/281 IONIC SEPARATION OR ANALYSIS
 250/282 .Methods
 250/283 ..With collection of ions

3 250/309 (3 OR, 0 XR)
 Class 250 : RADIANT ENERGY
 250/306 INSPECTION OF SOLIDS OR LIQUIDS BY CHARGED
 PARTICLES
 250/309 .Positive ion probe or microscope type

3 250/423R (1 OR, 2 XR)
 Class 250 : RADIANT ENERGY
 250/423R ION GENERATION

3 315/111.81 (0 OR, 3 XR)
 Class 315 : ELECTRIC LAMP AND DISCHARGE DEVICES: SYSTEMS
 315/111.01 DISCHARGE DEVICE LOAD WITH FLUENT MATERIAL
 SUPPLY TO THE DISCHARGE SPACE
 315/111.81 .Electron or ion source

2 118/715 (0 OR, 2 XR)
 Class 118 : COATING APPARATUS
 118/715 GAS OR VAPOR DEPOSITION

2 250/252.1 (2 OR, 0 XR)
 Class 250 : RADIANT ENERGY
 250/252.1 CALIBRATION OR STANDARDIZATION METHODS

2 250/298 (0 OR, 2 XR)
 Class 250 : RADIANT ENERGY
 250/281 IONIC SEPARATION OR ANALYSIS
 250/294 .Static field-type ion path-bending selecting
 means
 250/298 ..Magnetic field path-bending means

2 250/443.1 (0 OR, 2 XR)
 Class 250 : RADIANT ENERGY
 250/306 INSPECTION OF SOLIDS OR LIQUIDS BY CHARGED
 PARTICLES
 250/440.11 .Analyte supports
 250/443.1 ..With heat transfer or temperature-indication

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means

- 2 313/361.1 (0 OR, 2 XR)
Class 313 : ELECTRIC LAMP AND DISCHARGE DEVICES
313/359.1 WITH POSITIVE OR NEGATIVE ION ACCELERATION
313/361.1 .Means for deflecting or focusing
- 2 313/363.1 (0 OR, 2 XR)
Class 313 : ELECTRIC LAMP AND DISCHARGE DEVICES
313/359.1 WITH POSITIVE OR NEGATIVE ION ACCELERATION
313/363.1 .Extraction or target electrode
- 2 324/71.3 (1 OR, 1 XR)
Class 324 : ELECTRICITY: MEASURING AND TESTING
324/71.1 DETERMINING NONELECTRIC PROPERTIES BY MEASURING
G ELECTRIC PROPERTIES
324/71.3 .Beam of atomic particles
- 2 359/324 (0 OR, 2 XR)
Class 359 : OPTICS: SYSTEMS
359/237 OPTICAL MODULATOR
359/321 .Having particular chemical composition or structure
359/324 ..Magneto-optic crystal material
- 2 359/484 (2 OR, 0 XR)
Class 359 : OPTICS: SYSTEMS
359/483 POLARIZATION WITHOUT MODULATION
359/484 .Time invariant electric, magnetic, or
electromagnetic field responsive (e.g., electro-optical,
magneto-optical)
- 2 378/160 (1 OR, 1 XR)
Class 378 : X-RAY OR GAMMA RAY SYSTEMS OR DEVICES
378/145 BEAM CONTROL
378/160 .Shutter or chopper
- 2 427/523 (1 OR, 1 XR)
Class 427 : COATING PROCESSES
427/457 DIRECT APPLICATION OF ELECTRICAL, MAGNETIC,
WAVE, OR PARTICULATE ENERGY
427/523 .Ion plating or implantation